



Analytics for Compound Semiconductors

SiC in Focus

Steve Zamek 6/29/24

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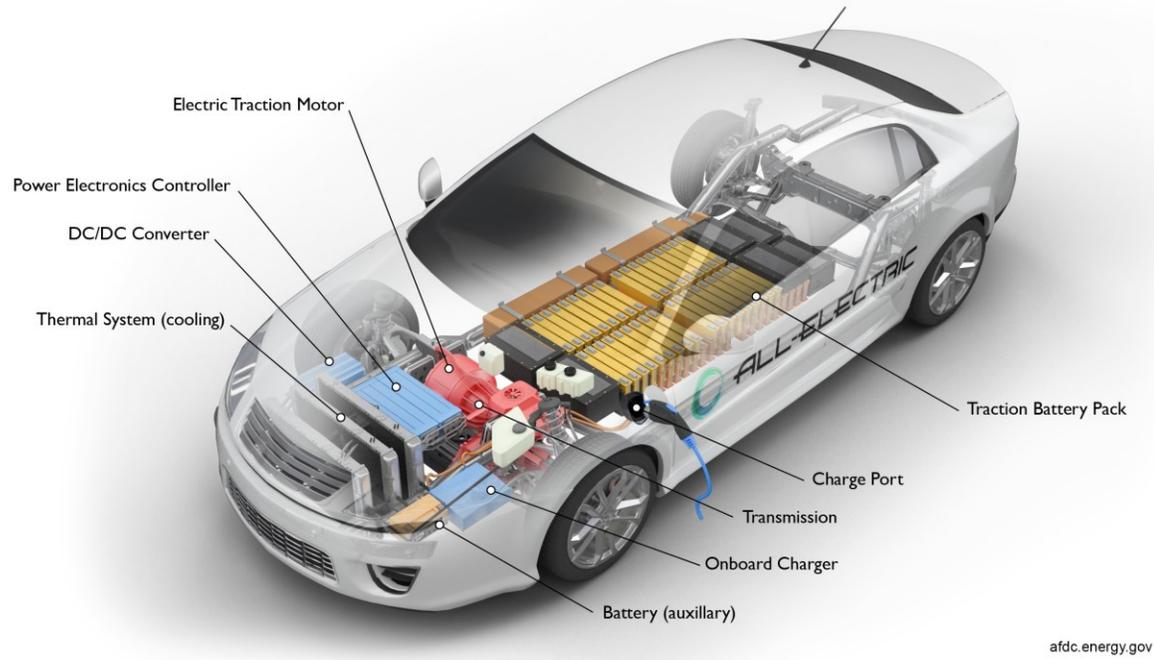
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SiC Industry at a Glance

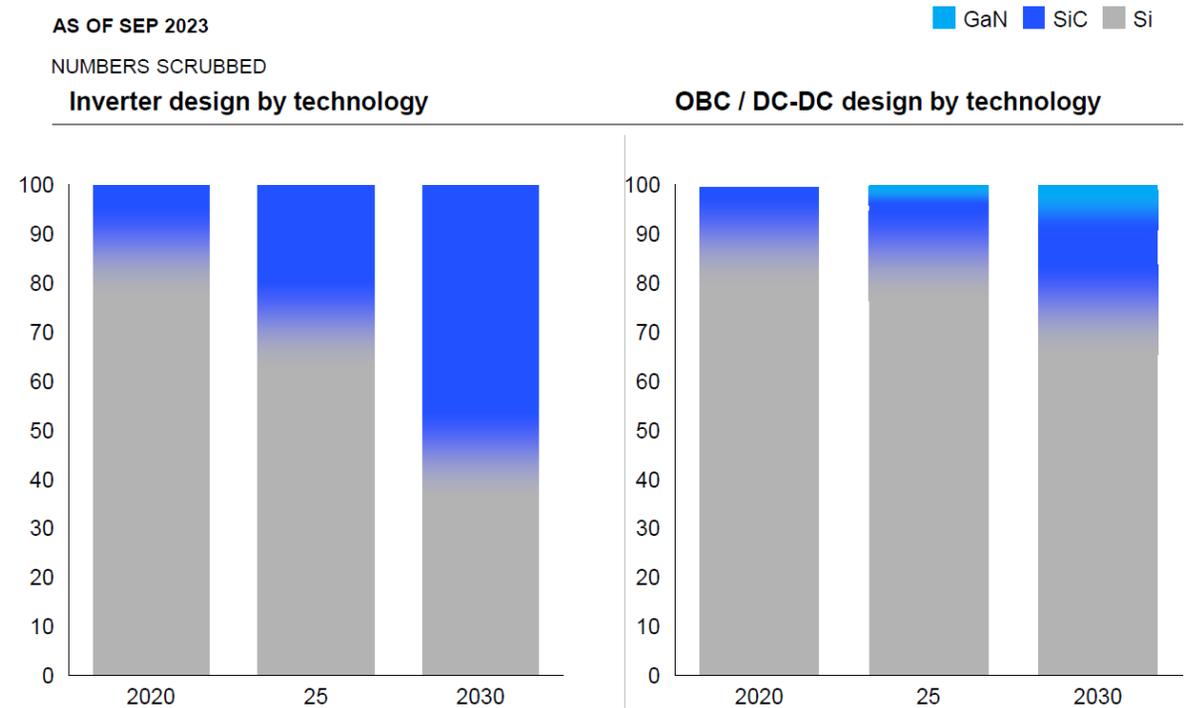
Demand driven mainly by Electric Vehicles

All-Electric Vehicle



source: <https://afdc.energy.gov/vehicles/how-do-all-electric-cars-work>

Projected 25x demand growth out to 2030

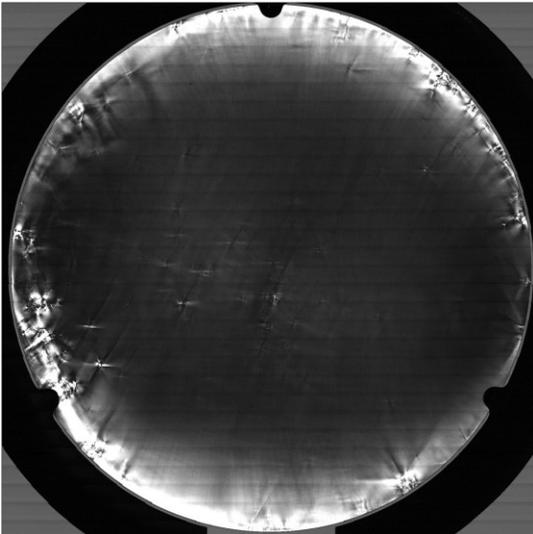


source: McKinsey Center for Future Mobility, Sep 2023

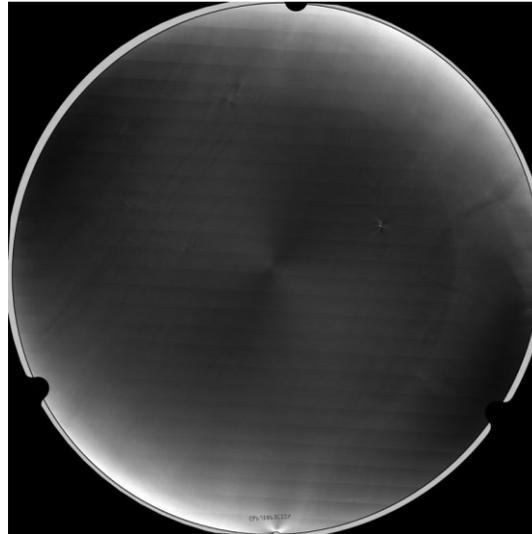
SiC Industry at a Glance

The next 10 years: substrate quality will remain a challenge as the industry is moving to 200 mm wafers

200 MM WAFER; XPOL IMAGE: 2019

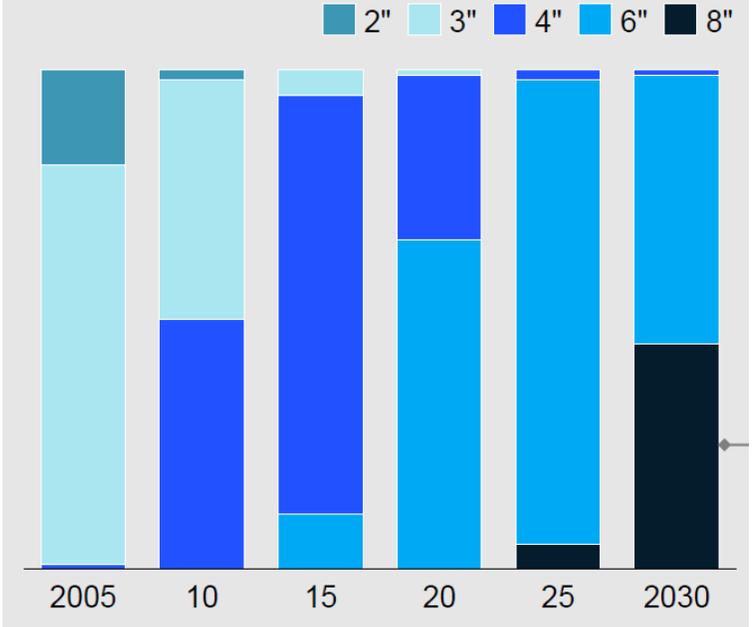


200 MM WAFER; XPOL IMAGE: 2022



source: Wolfspeed, SEMI Webinar, May 2023

SiC wafer diameter evolution, Annual capacity – 8" eqv. (K units), % of total SiC wafers shipped

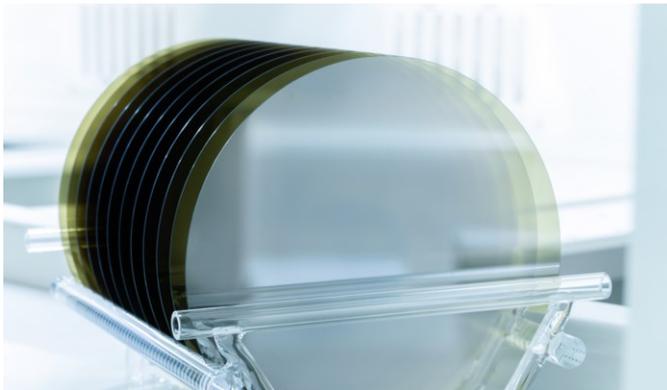


source: McKinsey Center for Future Mobility, Sep 2023

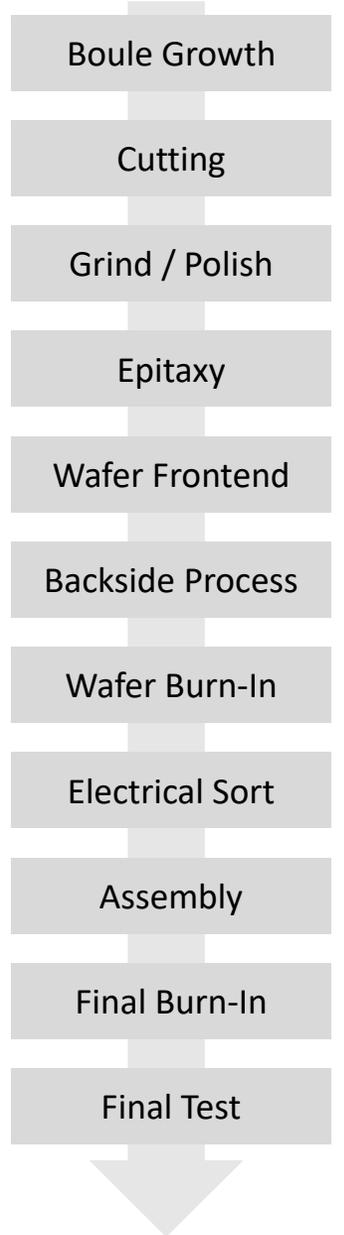
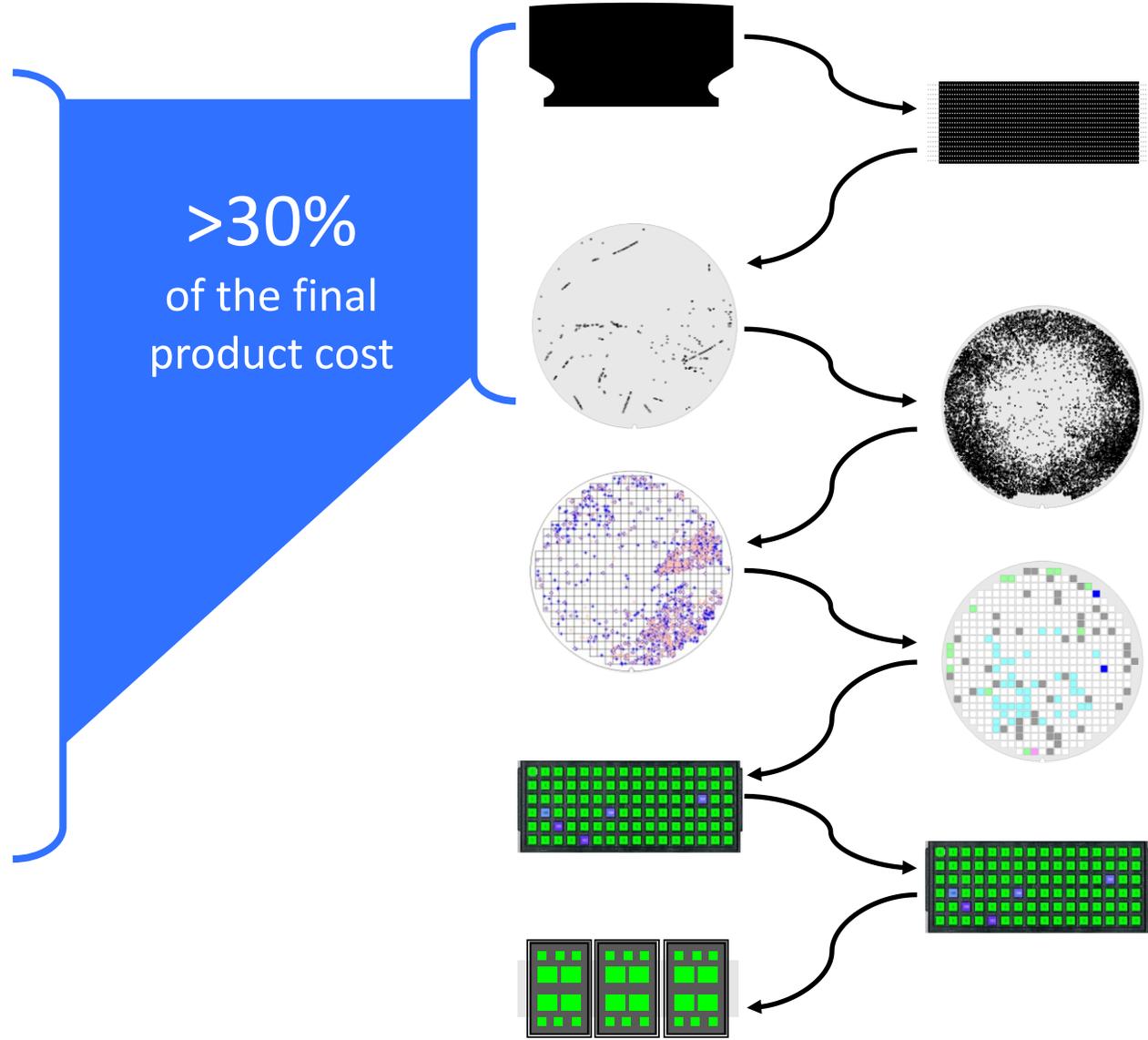
SiC Manufacturing Process Flow



source: CompoundSemiconductors.net, 2017

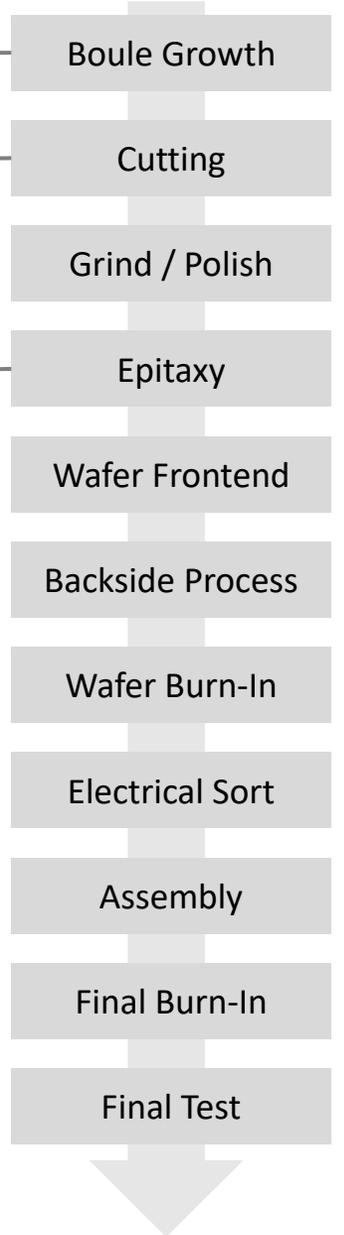
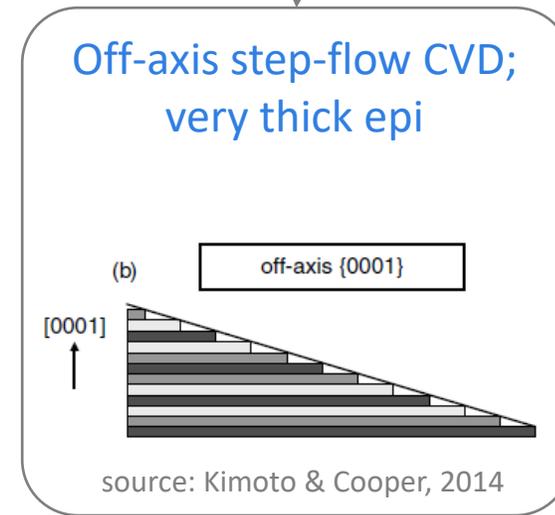
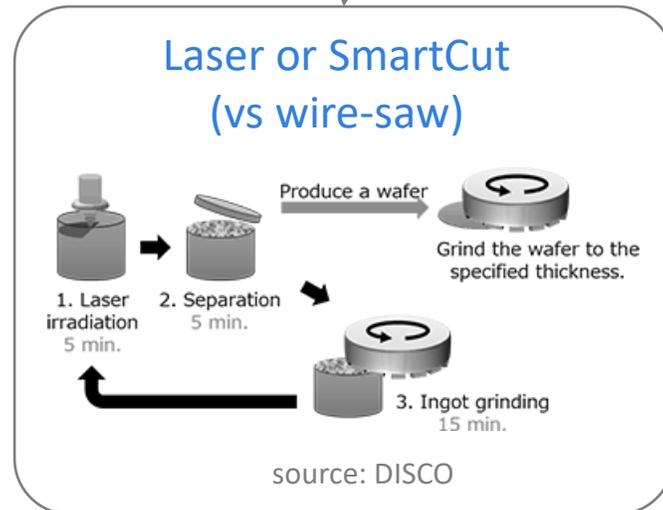
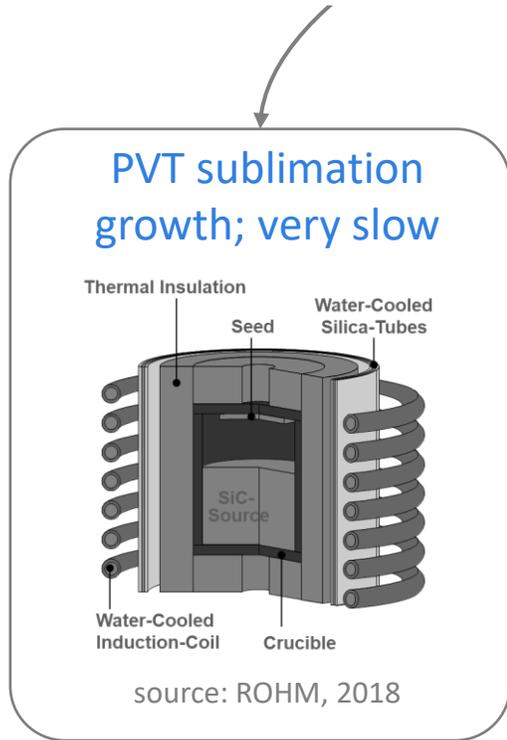


source: SICC, 2024



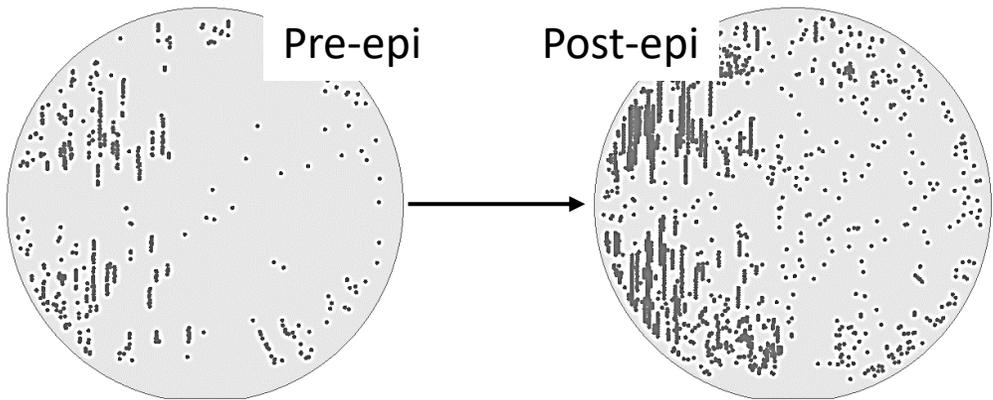
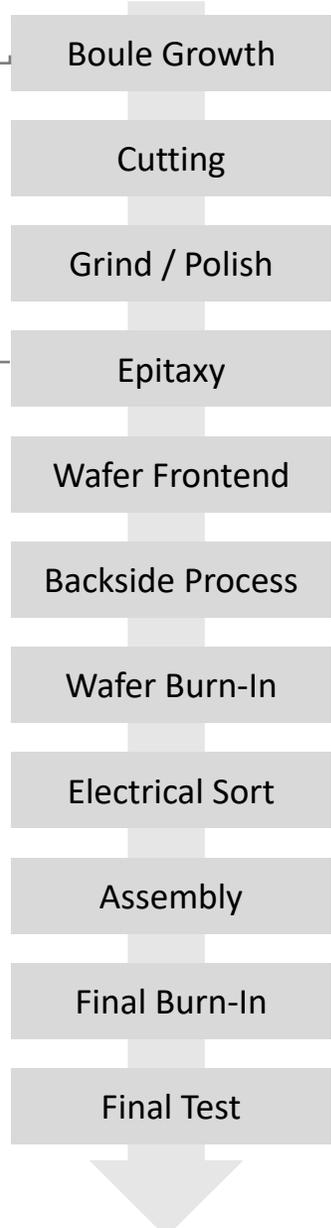
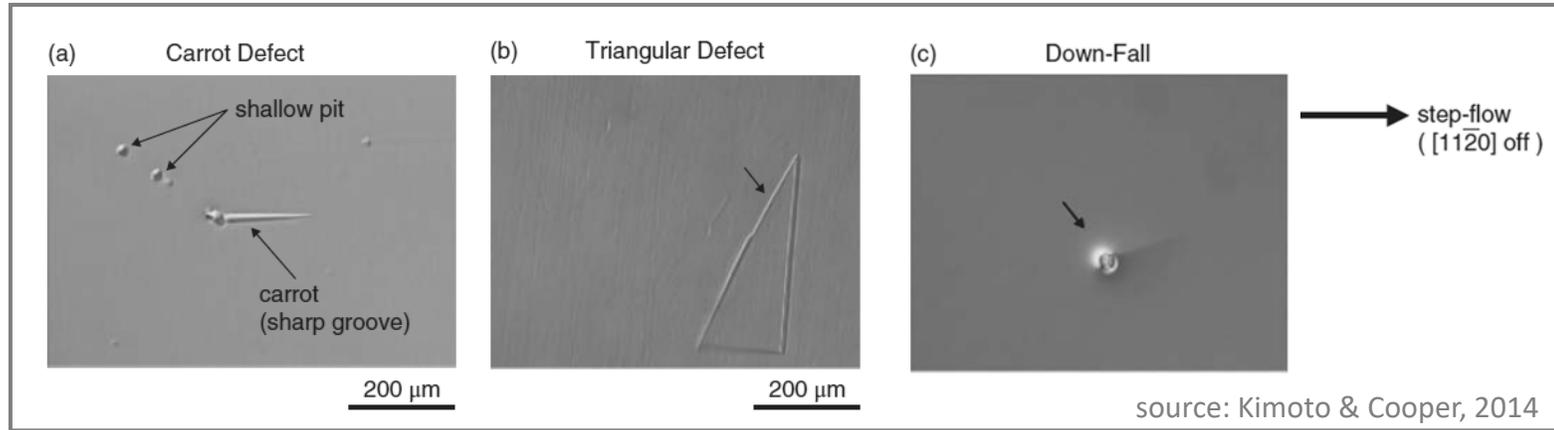
Challenges in SiC Manufacturing

SiC poses unique challenges to manufacturers with high defectivity at all steps

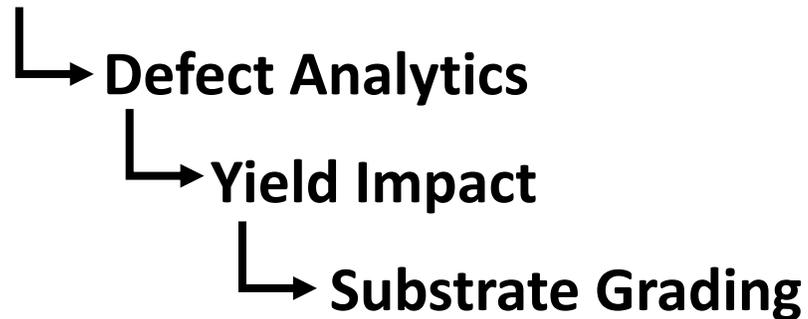


Unique Substrate Defects

Extended boule defects
 Micropipe
 Threading screw dislocation (TSD)
 Threading edge dislocation (TED)
 (Perfect) Basal plane dislocation (BPD)



Defect Inspection



Who We Are

Top 50 Equipment suppliers use Cimetrix by PDF for connectivity

Top 6 Foundries Run on PDF Solutions Technology

18 of Top 20 Semi Companies use PDF Solutions Products

>55K Fab tools connected using Cimetrix

>40K process tools under PDF process control across the ecosystem

>350 customers in 20 countries in Fables, IDM, Foundry, OSAT, and System

Leading solution for die traceability through the supply chain

Fastest growing company in manufacturing test operations



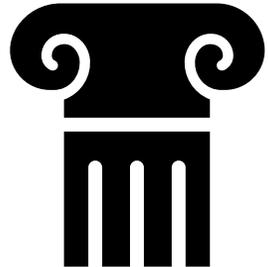
Our Solutions for SiC Manufacturing Analytics

“SiC is where silicon was decades ago...”

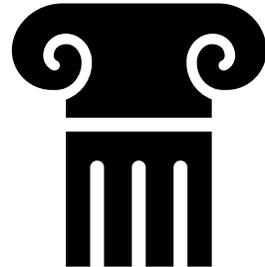


Accelerate your development with analytics

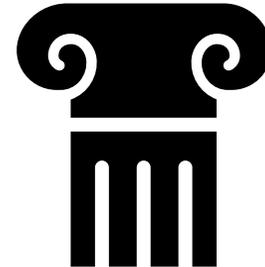
Solutions for Silicon Carbide Manufacturing



Equipment
Connectivity +
Process Control



Inline + Test Data
Management
Defect | Binmap



Lot Genealogy +
Wafer Level
Traceability



ModelOps
with AI/ML

How We Do It

Proven track-record of interfacing with majority of Manufacturing Execution Systems

Material Hierarchy	Meta Data	Equipment History
Technology	Equipment	Equipment
Family	Operator	TrackIn/Out
Process	Program	Recipe
Product	Recipe	Operator
Source Lot	Date/Time	Chamber
Lot	Process Flow	Rework
Wafer #	Stages	Reticle
Die	Steps	

CamStar
 PROMIS
 Oracle
 IBM Si View
 WorkStream
 FACTORYWorks
 StationWorks
 Wonderware
 Miracom
 APEX
 ...

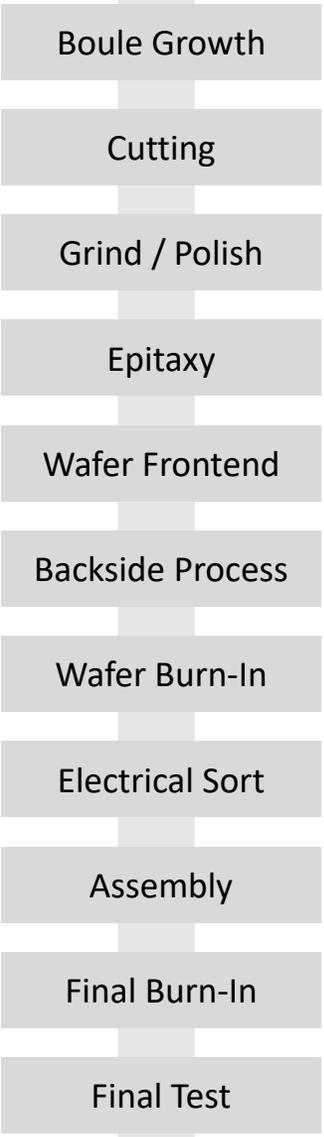


**Inline Data
 Defect & Metrology**

**Equipment Sensor
 Data (FDC)**

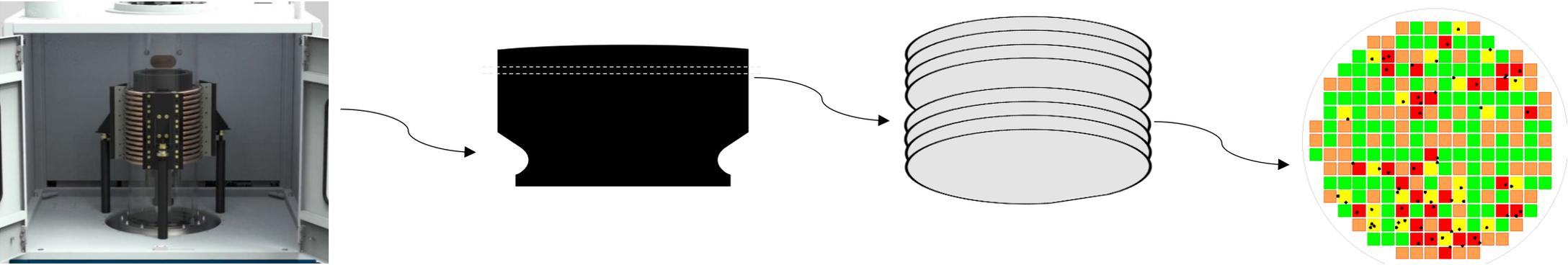
**Electrical Data:
 PCM | WAT | Binmap**

**Assembly Data
 Die Level Traceability | E142**



**Big Data
 Manufacturing
 Analytics platform**

Exensio™ Equipment Process Control for SiC

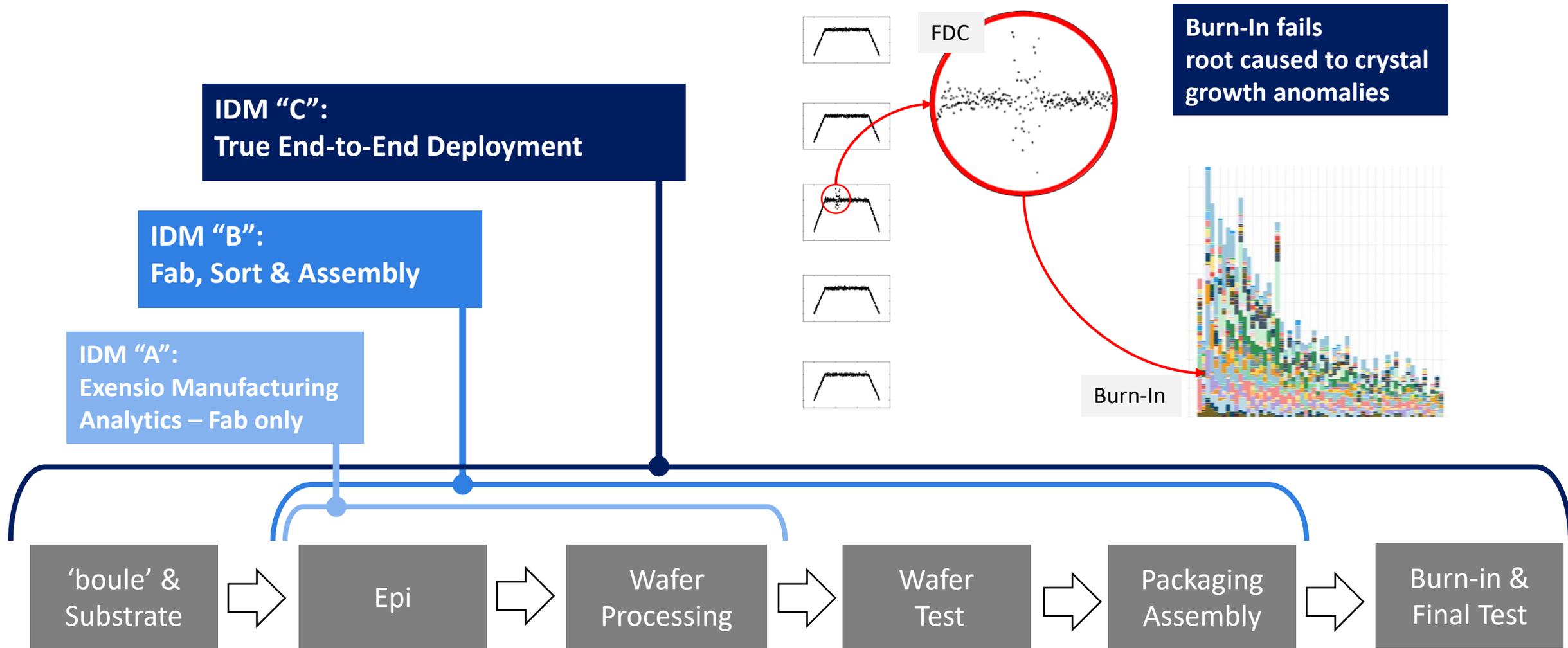


Bring all data under one roof
Use modern data analytics

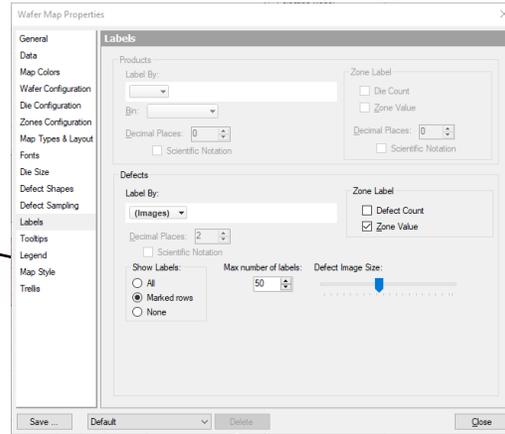
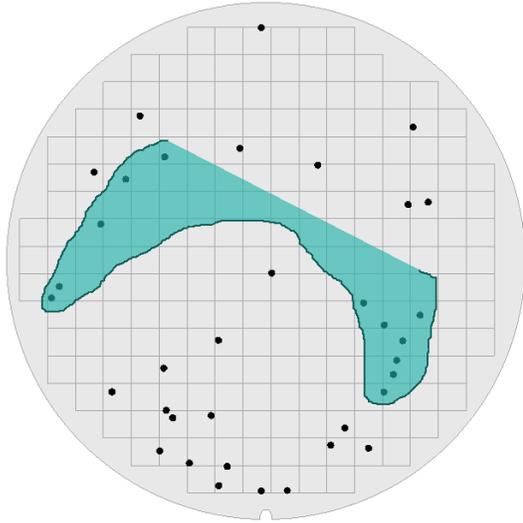


Establish correlations
Identify root-cause of low yield

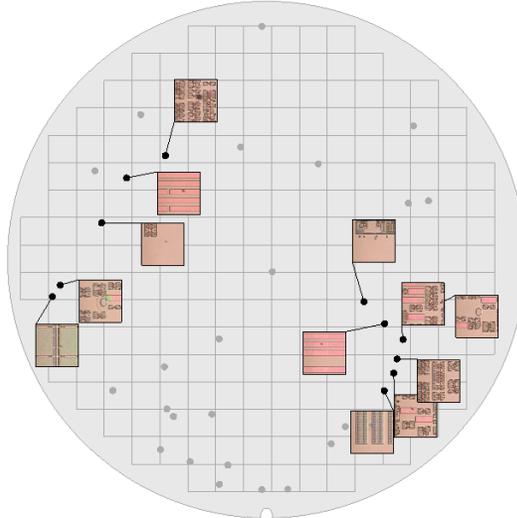
Deployment Examples in SiC Manufacturing



Defect Management Tools



- Powerful tools:**
- Selections
- Markings
- Labeling
- Sampling



Defect classification

Filter by: Name Filter string:

Method: manual Tag by name: 1

Add if not found

Code	Name	Critical
-2	1	Y
-2	10	Y
-2	101	Y
-2	102	Y
-2	11	Y
-2	111	Y
-2	112	Y
-2	113	Y
-2	17	Y
-2	19	Y
-2	2	Y
-2	200	Y
-2	22	Y
-2	226	Y

Move to next row Refresh after commit

Commit

- Defects can be reclassified
- Newly generated defects can be exported into new KLARF
- Defect class codes can be redefined in the database

Defect image gallery

Defect : 1, Processing Step : LYR1, size : 3.99299999039333, layer_of_origin : LYR1, roughbin : roughbin_1, finebin : finebin_245

Defect : 5, Processing Step : LYR1, size : 0.624000012874603, layer_of_origin : LYR1, roughbin : roughbin_3, finebin : finebin_245

Defect : 6, Processing Step : LYR1, size : 1.8719997901917, layer_of_origin : LYR1, roughbin : roughbin_1, finebin : finebin_245

Defect : 7, Processing Step : LYR1, size : 0.624000012874603, layer_of_origin : LYR1, roughbin : roughbin_2, finebin : finebin_245

Data table : Defect

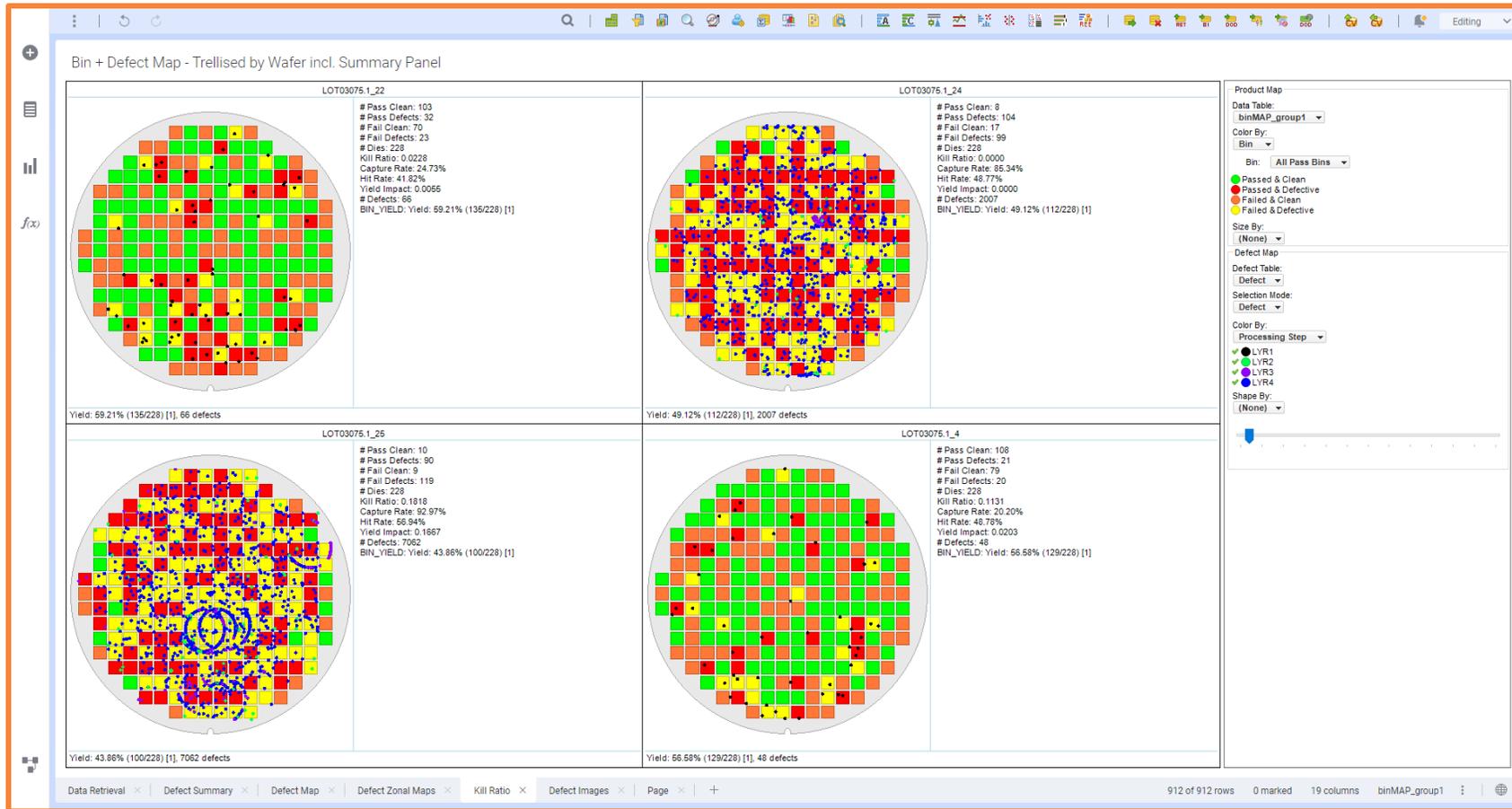
Marking : Marking

Filters : Source (All) 5 values Unknown SEM Internal SEM External FDX

Image Adjustments : Brightness Contrast Gray Scale Invert Colors Reset

Fill 100% 27%

Defect | Binmap Overlays



	Passed_Clean
	Passed_Defective
	Failed_Clean
	Failed_Defective

Wafer Map Properties

General

Data

Map Colors

Map Vectors

Wafer Configuration

Die Configuration

Zones Configuration

Map Types & Layout

Fonts

Die Size

Defect Shapes

Defect Sampling

Labels

Tooltips

Legend

Map Style

Trellis

Map Colors

Wafer Colors Defect Colors

Columns: Bin All Pass Bins Settings ...

Color mode: Categorical Group By: Linear Groups: 6

- Passed_Clean
- Passed_Defective
- Failed_Clean
- Failed_Defective

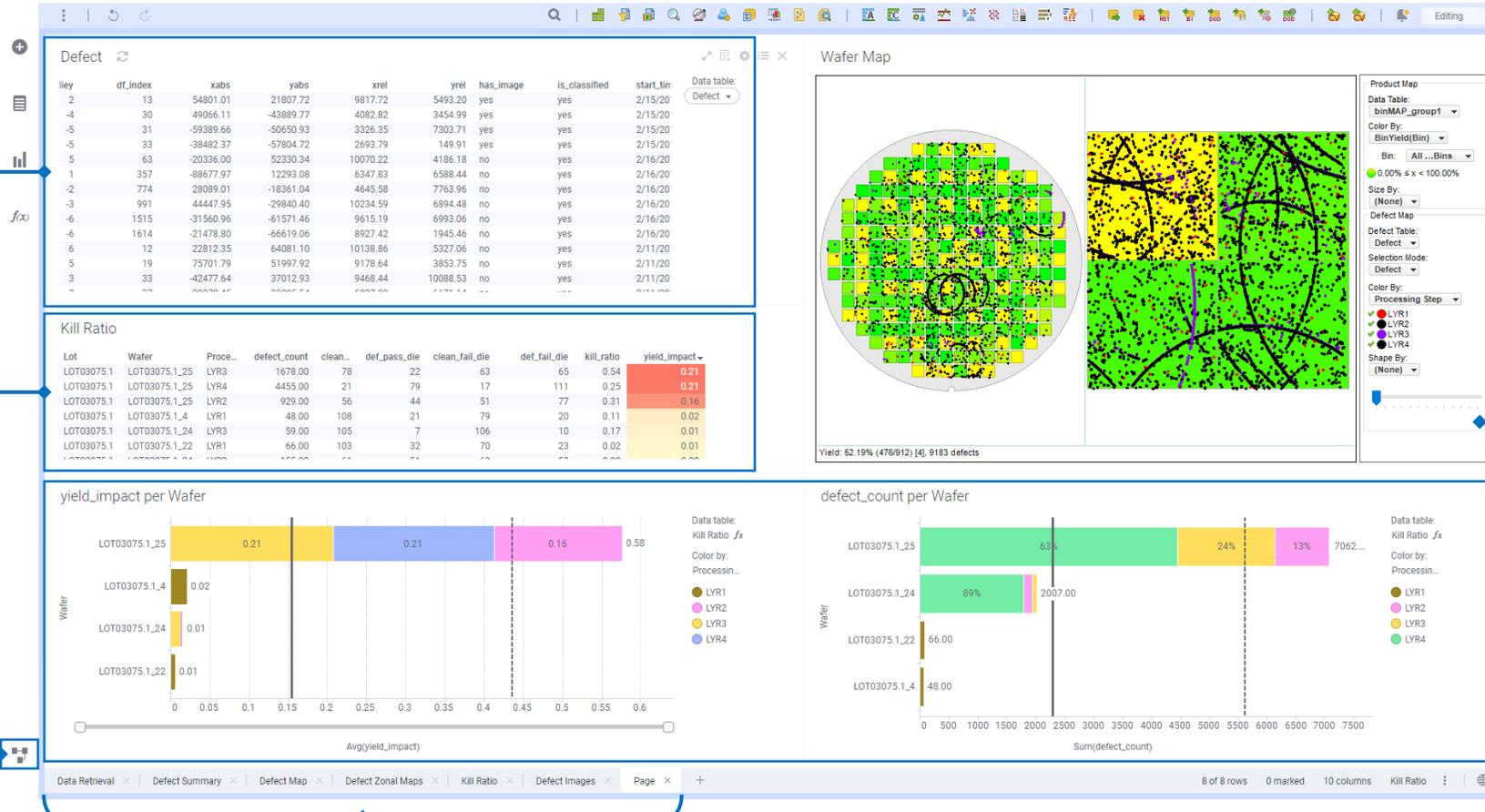
Color by defect overlay when trellis by wafer

Product Map Transparency when Overlaid

Save ... Default Delete Close

Defect | Binmap Overlays

Raw defect data



Overlays: defects on pass/fail die binmap
Stacking at lot, wafer, reticle, and die level

Defect summaries & statistics: CR, KR, YI, ...

Defect drill-downs

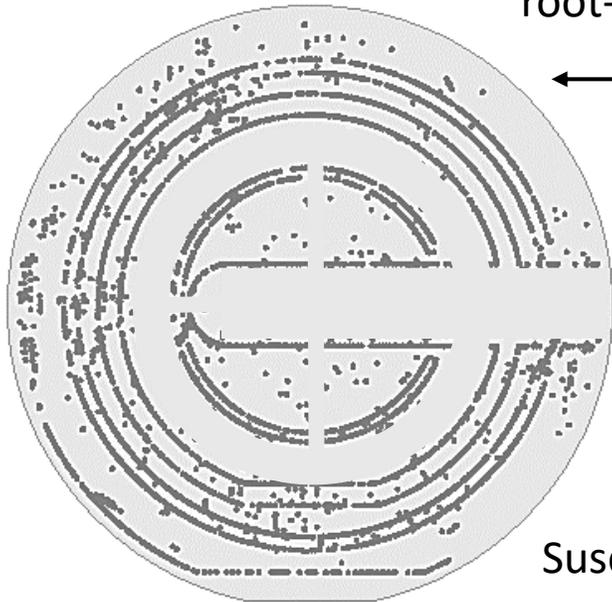
Intuitive data panel

Many more pages with fully customizable visualizations and analysis types

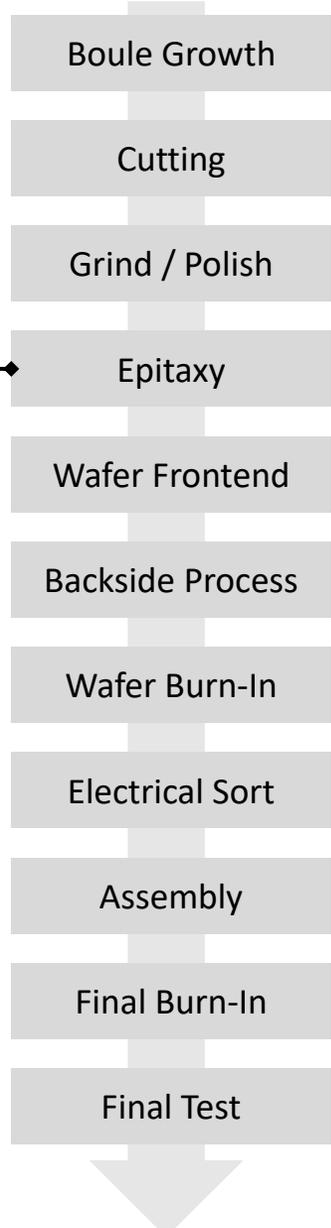
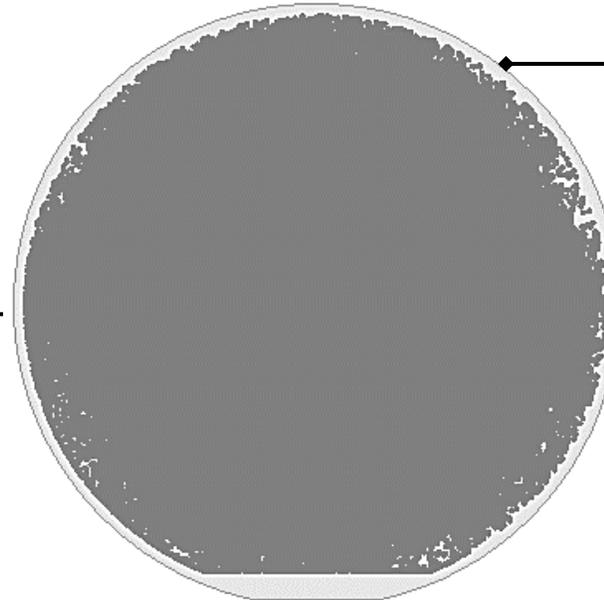
Exensio™ Defect Management for SiC

Customer use case: identified root-cause of killer defects

Defect rebinning by size reveals root-cause for killer defects



Susceptor pattern emerges



Summary

■ The next 5 years in SiC

- SiC CAGR outpaces semiconductors as a whole
- Defectivity will remain high
- Steeper challenges in transition to 200 mm wafers

■ Our solutions

- Exensio is the #1 platform for data analytics across semiconductor manufacturing
- Continued adoption for SiC
- Those with end-to-end deployments will grow faster



Product portfolio:

- Equipment connectivity
- Manufacturing analytics
- Process Control
- Test Operations
- Assembly Operations
- AI & ModelOps

Services:

- Data Integration
- Site, tools, data audit
- Building templates
- Classes and training

Thank You

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